

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

4	DEMARKE				
	APPLICANT:	YOUNG-HOON PARK)		
			,)	Group Art Unit:	
	SERIAL NUMBER:	09/848,577		1763	#7. B
)		12/19/02
	FILED:	May 3, 2001	,)	Examiner:	Mu
		,)	Karlaa Moore.	• • •
	FOR:	REACTOR FOR DEPOSITING)		
		THIN FILM ON WAFER)	••	

Commissioner of Patents and Trademarks Washington, D.C.

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DEC 1 7 2002

TC 1700

Dear Sir:

This amendment with remarks is submitted in response to an Office Action dated September 11, 2002. Applicant requests reconsideration of the outstanding rejection in view of the following remarks and amendments.

AMENDMENT

IS BEING DEPOSITED WITH THE UNITED STATES
POSTAL SERVICE AS FIRST CLASS MAIL IN AN

IN THE CLAIMS:

Please enter the following newly added claims.

The thin film deposition reactor of claim 1, wherein an interval 18. (Newly Added) between a center of the diffusion plate and the wafer block is different from an interval between edges of the diffusion plate and the wafer block. (671V/ 1/4)

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